

REMARKS/ARGUMENTS

Claims 1, 2, 5-10, 14-19 and 23-26 remain in this application. Claims 1, 2, 6-10 and 19 have been amended to overcome the Examiner's rejections based upon prior art. Claims 3, 4, 11-13 and 20-22 have been cancelled. Accordingly, reconsideration is requested since none of the prior art discloses the present invention.

Claim 1 has been amended to include the limitations of Claim 4, which the Examiner had indicated was directed to allowable subject matter, and has been additionally amended to delete reference to the "photoresist" masked array and the "inductively coupled" plasma dry etching process as being unduly limiting in view of the prior art. Claim 1 as presently written is directed to a method for fabricating a field emitter tip including the step of shaping a group III-nitride semiconductor into a field emitter tip using a plasma dry etching process wherein said plasma dry etching process creates an anisotropic deep etch in the group III-nitride semiconductor layer followed by an isotropic etch in the group III-nitride semiconductor layer to create generally pointed tips on the group III-nitride semiconductor layer. Accordingly, Claim 1 is considered to be patentable over Jiang et al alone or taken in combination with Chowdhury et al.

Claim 10 has been amended to include the limitations of Claim 13, and Claim 19 has been amended to include the limitations of Claim 22, which the Examiner had indicated were directed to allowable subject matter. Accordingly, Claims 10 and 19 are likewise considered to be patentable over Jiang et al alone or taken in combination with Chowdhury et al.

Claims 2 and 5-9 depend from Claim 1 and are patentable over the prior art of record for the reasons given in support of the patentability of Claim 1 as well as for the additional recitations recited therein. Claims 14-18 depend from Claim 10 and are patentable over the prior art of record for the reasons given in support of the patentability of Claim 10 as well as for the additional recitations recited therein. Claims 23-26 depend from Claim 19 and are patentable over the prior art of record for the reasons given in support of the patentability of Claim 19 as well as for the additional recitations recited therein.

For the above reasons, Claims 1, 2, 5-10, 14-19 and 23-26 are considered allowable over the prior art of record and an early notice to such effect is solicited.

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